

APR 25 2005

1270.43264X00

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: H. KOMATSU

Application No.: 10/701,448

Filed: November 6, 2003

For: PHOTSENSITIVE RESIN COMPOSITION, PROCESS FOR
FORMING RELIEF PATTERN, AND ELECTRONIC
COMPONENTArt Unit: 1752
Examiner: H. Le
Confirmation No. 7624**AMENDMENT**Mail Stop: Amendment - Fee
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

April 25, 2005

Sir:

In response to the Office Action mailed November 23, 2004, the period for response having been extended for two months by the attached Petition for Extension of Time, please amend the above-identified application as listed in the following, and as set forth on the following pages:

AMENDMENTS TO THE CLAIMS; and

REMARKS are included following the amendments.